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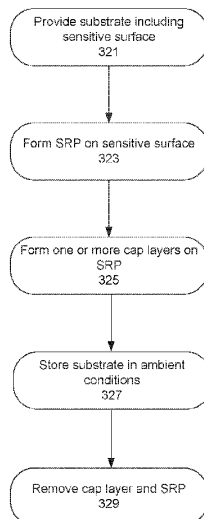
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(54) Title: STIMULUS RESPONSIVE POLYMER FILMS AND FORMULATIONS



(57) Abstract: Formulations for forming stimulus responsive polymers (SRPs) on semiconductor sub-
strates include organic weak acids. Methods of protecting sensitive substrates including forming an SRP
layer on sensitive substrates and forming one or more cap layers on the SRP layer.

FIG. 3

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